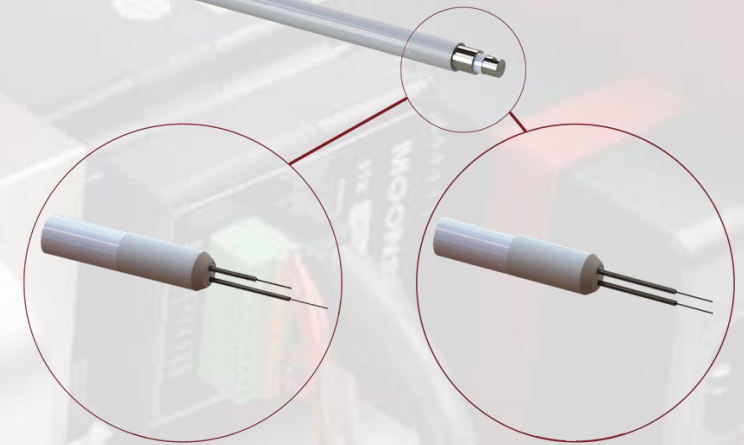


# LANGMUIR PROBE SYSTEM

Measure the fundamental plasma parameters with the industry standard Langmuir Probe

<https://www.impedans.com/langmuir-probe>



# The Langmuir Probe System

Measure the fundamental plasma parameters with the industry standard Langmuir Probe

## Parameters Measured:

- ✓ Plasma potential
- ✓ Floating Potential
- ✓ Charged Particle Densities (ions and electrons)
- ✓ Electron Temperature
- ✓ Electron Energy Probability Function (EEPF)
- ✓ All of the above can automatically be measured spatially with the linear drive addition

## Advantages of the Impedans Langmuir Probe:

- ✓ 80 MHz sampling rate, allowing for plasma characterization with  $\mu\text{s}$  resolution during pulsing
- ✓ Single and double probe exchangeable head
- ✓ RF compensated for up to 5 frequencies
- ✓ State of the art plasma models built into the software for automatic data analysis
- ✓ Over 100 publications using this hardware, trusted by universities and industry alike: [impedans.com/langmuir-applications](https://impedans.com/langmuir-applications)



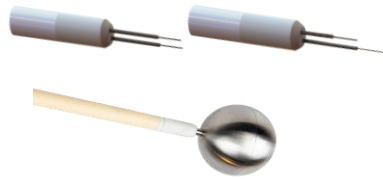
Langmuir Probe System with Single and Double Tips



Langmuir Probe System with Linear Drive

# Key Features

## Interchangeable probe heads



## Compatible with majority of plasma excitation methods

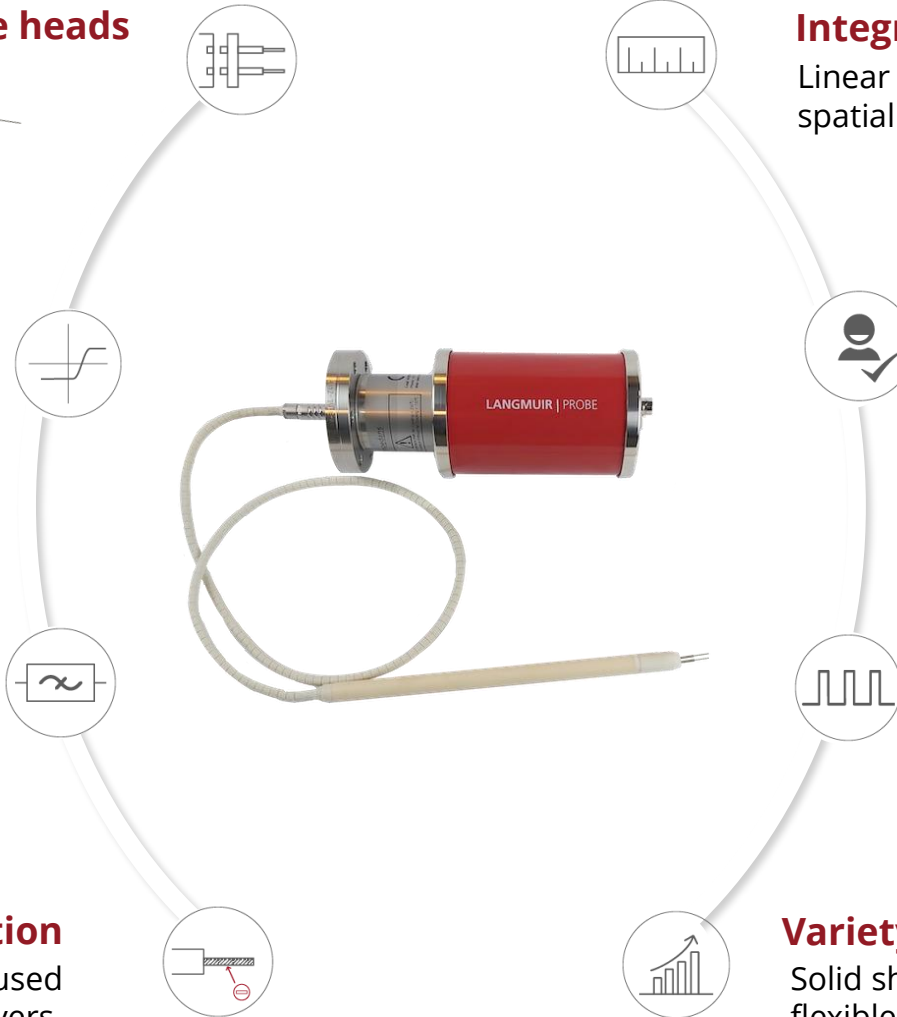
DC, pulsed DC, RF, pulsed RF, microwave and other plasma excitation methods.

## Integrated RF compensation filters

RF compensated up to 5 frequencies in one probe.

## Automated tip cleaning function

Plasma electron bombardment is used to remove oxides and insulating layers.



## Integrated linear drive mechanism

Linear drive mechanism provides automatic spatial plasma uniformity.

## Advanced software

State of the art plasma models built into software for automatic data analysis. Intuitive and user friendly

## External pulse synchronization

Time averaged, time trend, synchronized pulse profile and triggered fast-sweep modes.

## Variety of Probe Options

Solid shaft (standard and high temperature), flexible and substrate-level sensors available to serve many plasma chamber geometries

# Technical Specifications

Parameters Measured	Range
Sampling Rate	80 MHz
Floating Potential	-145 V to +145 V
Plasma Potential	-100 V to +145 V
Plasma Density	$10^6$ to $10^{13} \text{ cm}^{-3}$
Ion Current Density	$1 \mu\text{A}/\text{cm}^2$ to $300 \text{ mA}/\text{cm}^2$
Electron Temperature	0.1 eV to 15 eV
EEPF (Electron Energy Probability Function)	0 eV to 100 eV

- ✓ For more detailed specifications and different models available, visit <https://www.impedans.com/langmuir-probe>
- ✓ To see if the probe is suitable for your plasma application, see the applications list at [impedans.com/langmuir-applications](https://www.impedans.com/langmuir-applications)
- ✓ To arrange a technical discussion, contact [support@impedans.com](mailto:support@impedans.com)



# Technical Specifications

Probe Specifications	Range
Probe shaft diameters available	10 mm (standard), 6.5 mm (high temp, single)
Probe tip materials available	Tungsten (Noble); Tantalum and Platinum (Reactive, ex. Oxygen)
Probe types	Single with DC Reference, Double, Mach, Spherical, Planar (10 mm shaft), Single (6.5 mm shaft)
Vacuum Flanges	CF40 default; Adaptors on request; Adjustable flanges available
Temperature Limits	230C ( <i>Air cooled</i> ), 125C ( <i>No cooling</i> ), 900C (6.5 mm)
RF Compensation	Up to 5 filters (10 mm)
TTL input trigger; Time Resolution	1 Hz to 1 MHz; 12.5 ns (no filters), 1 us (filters)
Accessories	Right angle adaptors; 4 mm shaft
Pressure Range	Max 10 Torr (Single, Planar, Spherical), Max atmospheric (Double, Mach)



Right Angle Adaptor

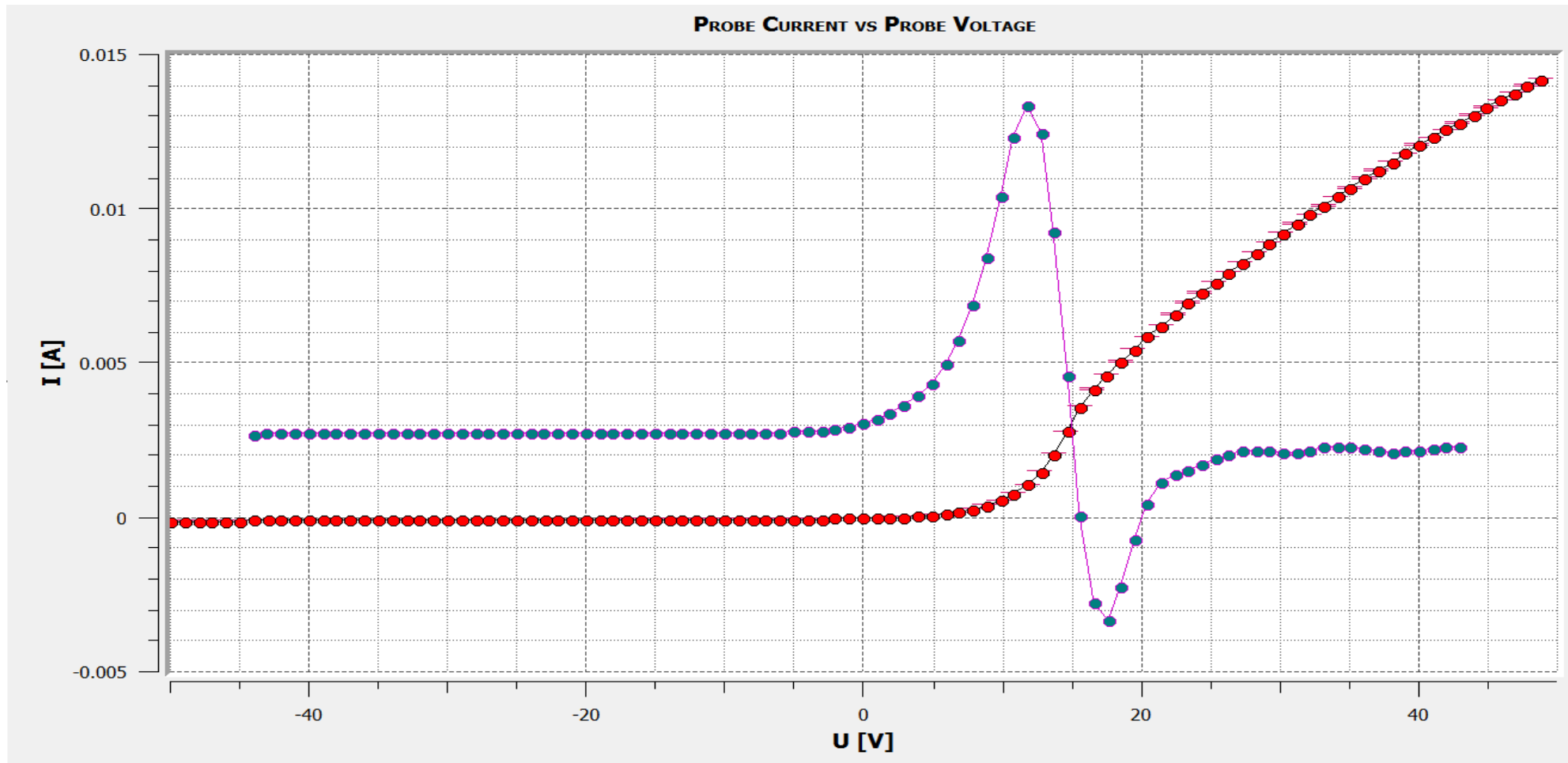


4 mm shaft adaptor



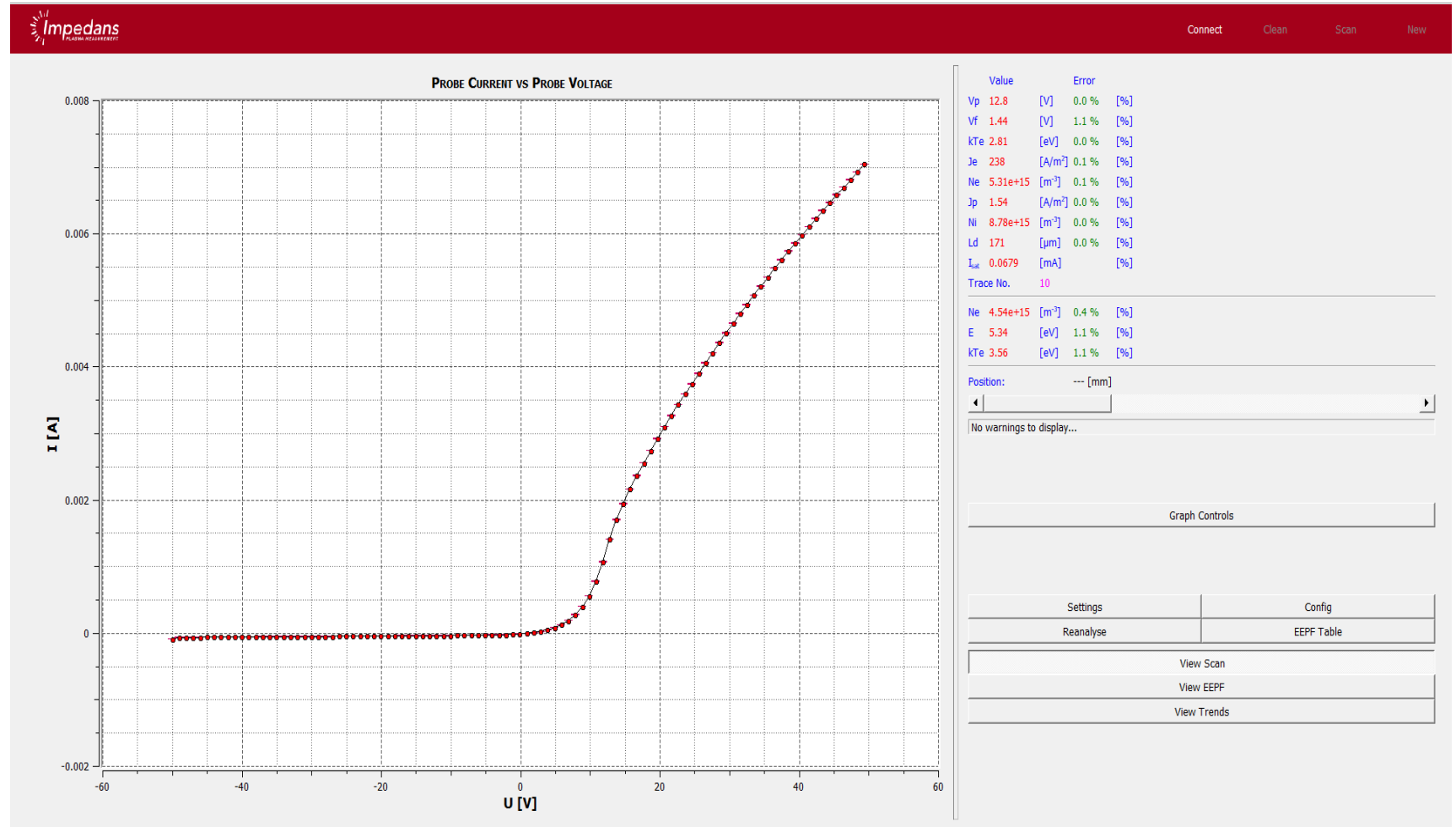
Langmuir Probe with an Adjustable Flange

# Example Data: VI curve and second derivative for a Single Probe

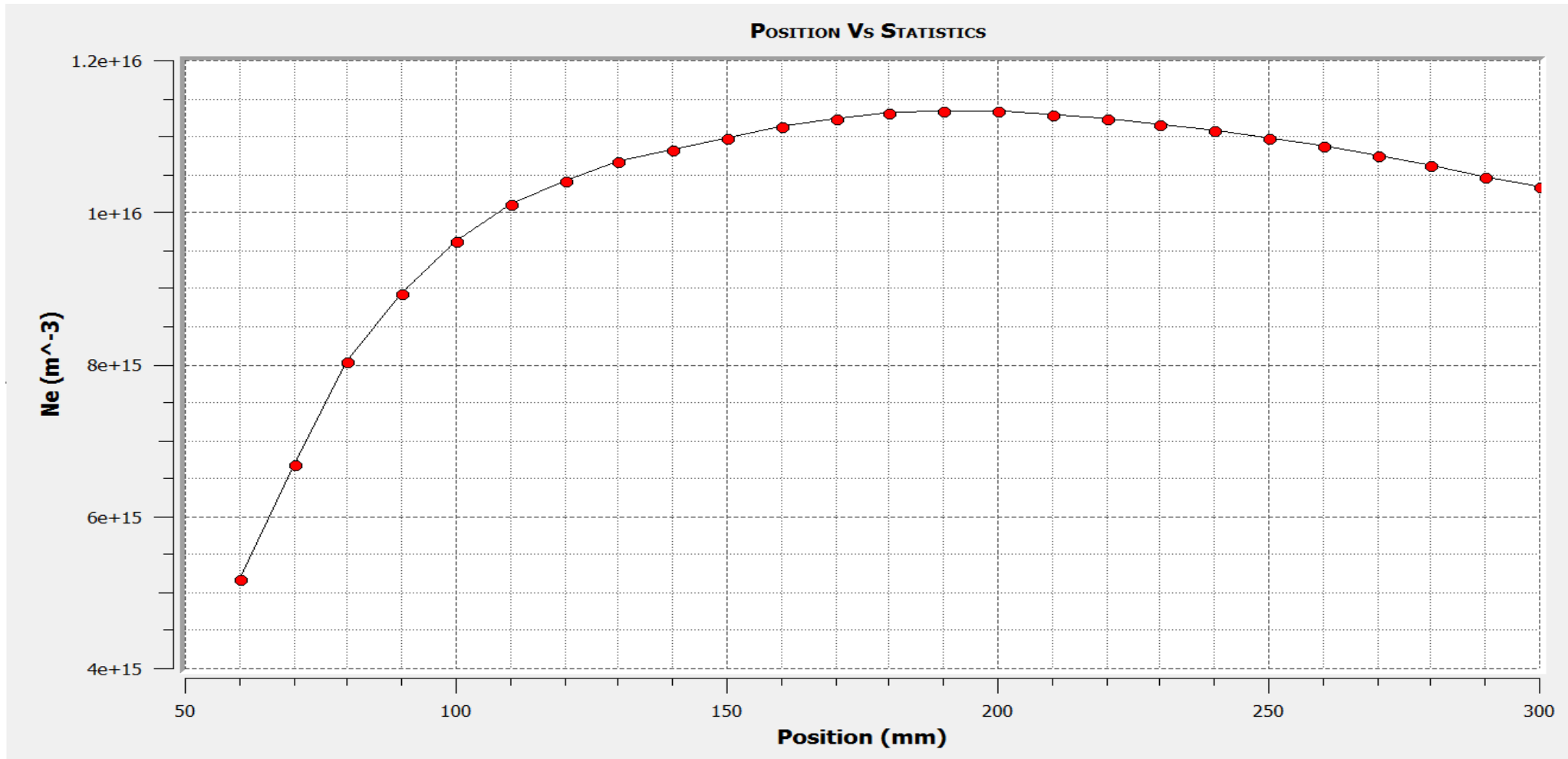


# Example Data: Single Probe Parameters

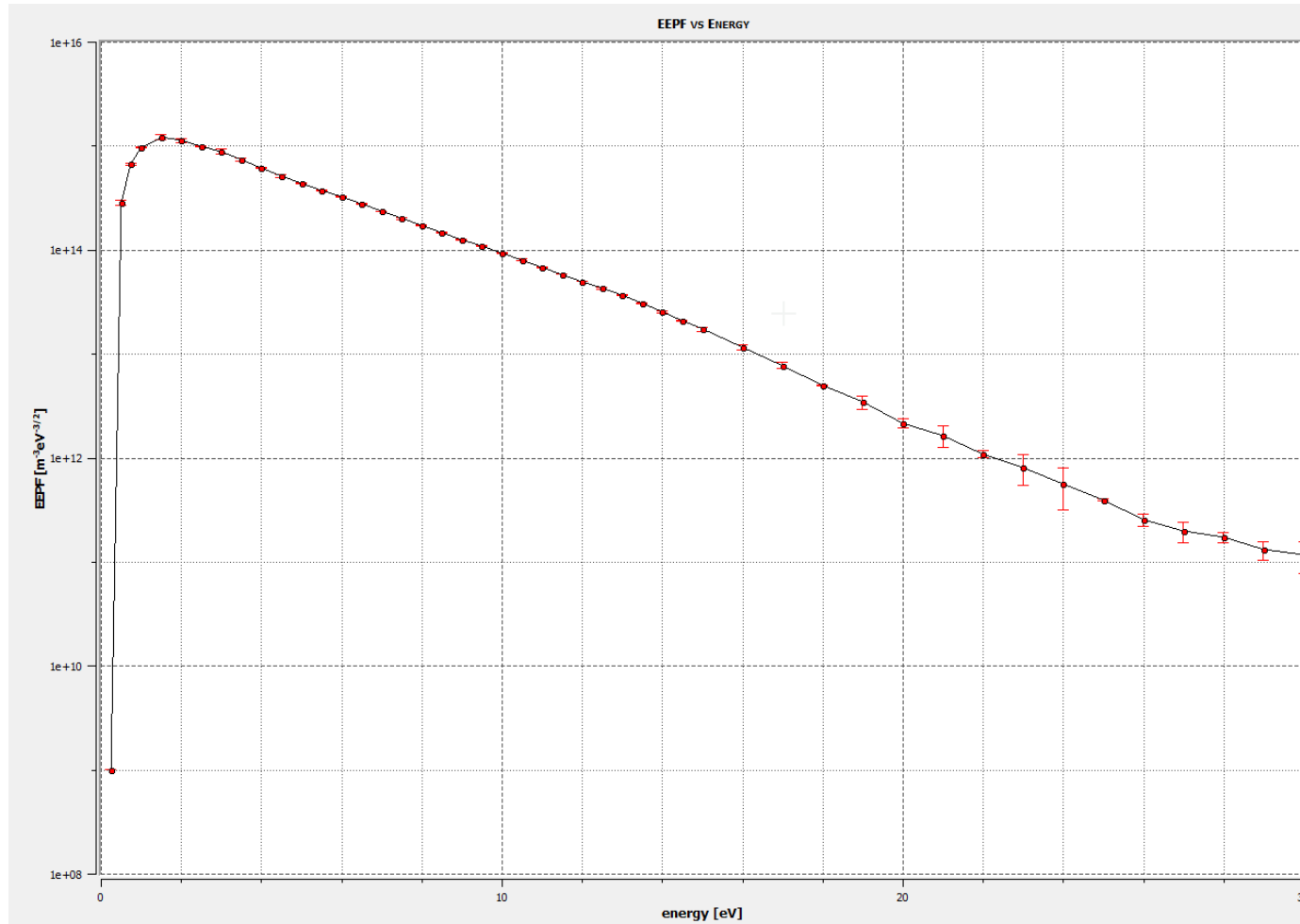
- ✓ Plasma Potential ( $V_p$ )
- ✓ Floating Potential ( $V_f$ )
- ✓ Electron Temperature ( $kT_e$ )
- ✓ Electron Current Density/Flux ( $J_e$ )
- ✓ Electron Density ( $N_e$ )
- ✓ Ion Current Density/Flux ( $J_p$ )
- ✓ Ion Density ( $N_i$ )
- ✓ Debye Length ( $L_d$ )
- ✓ Ion Saturation Current ( $I_{sat}$ )



# Example Data: Electron Density as a function of position over a 300mm wafer



# Example Data: Electron Energy Probability Function (EEPF)



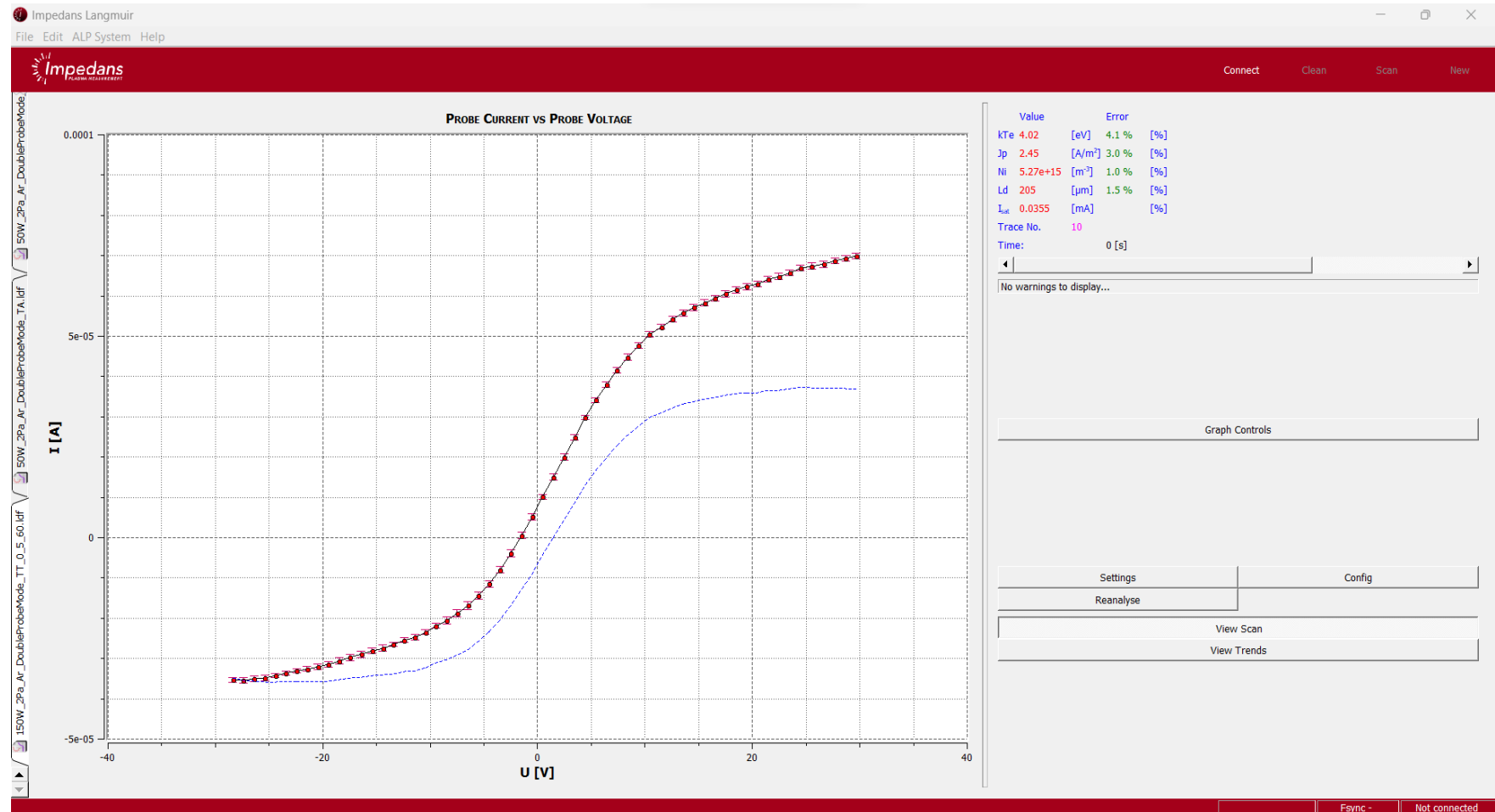
Edit EEPF Table saved with data

Energy	Resolution
17	1
18	1
19	1
20	1
21	1
22	2
23	2
24	2
25	3
26	3
27	3
28	4
29	4
30	4

Buttons: Add, Remove, OK, Cancel

# Example Data: Double Probe Parameters

- ✗ Plasma Potential ( $V_p$ )
- ✗ Electron Current Density/Flux ( $J_e$ )
- ✗ Electron Density ( $N_e$ )
- ✗ Floating Potential ( $V_f$ )
- ✓ Electron Temperature ( $kT_e$ )
- ✓ Ion Current Density/Flux ( $J_p$ )
- ✓ Ion Density ( $N_i$ )
- ✓ Debye Length ( $L_d$ )
- ✓ Ion Saturation Current ( $I_{sat}$ )



# Langmuir Applications

# Measurement of Microsecond Resolution Electron Density Evolution in a Pulsed ICP

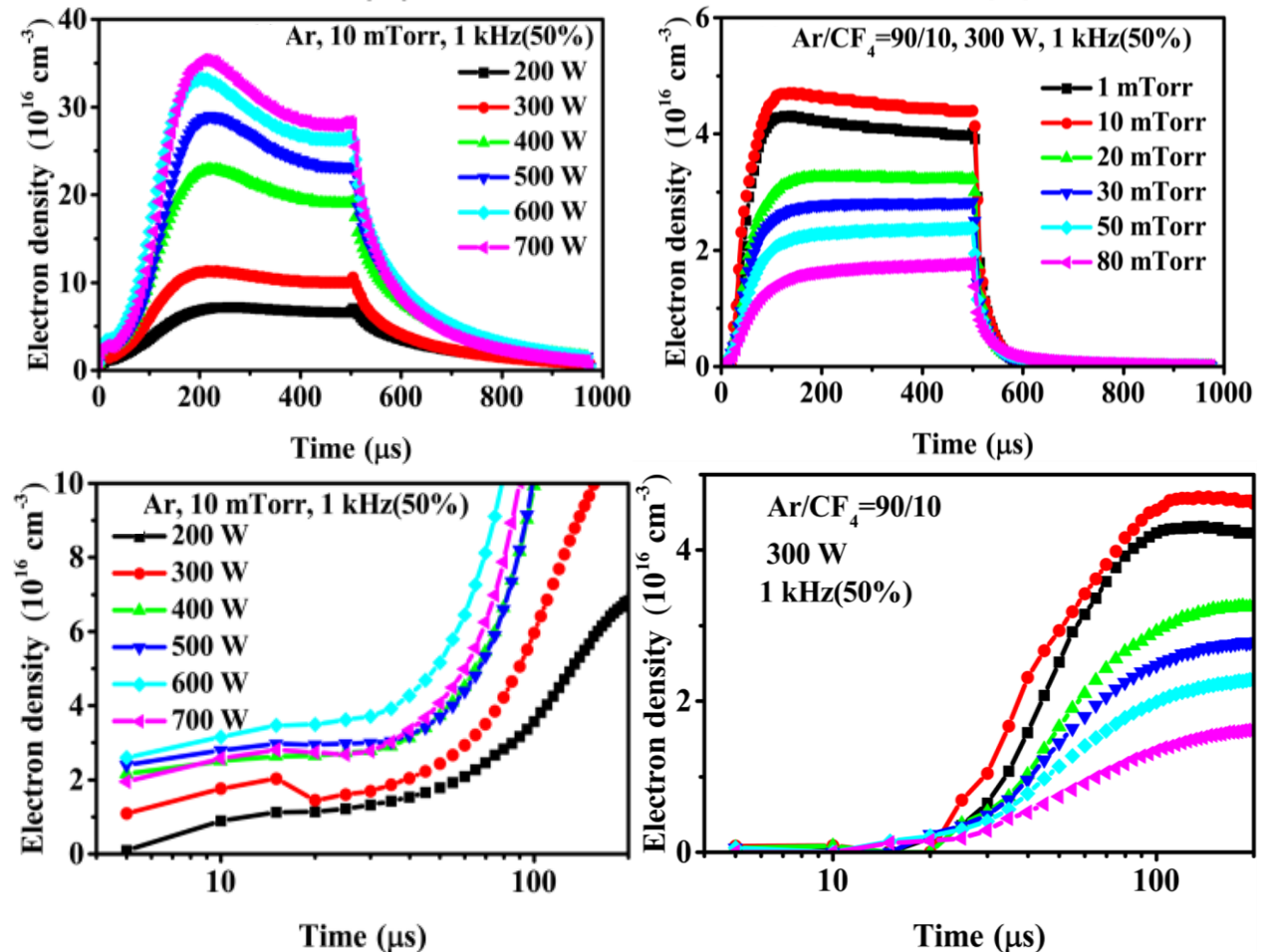
## Complex Transients of Input Power and Electron Density in Pulsed Inductively Coupled Discharge

DOI: 10.1063/1.5114661

The objective of this paper was to measure, on a microsecond timescale, the evolution of the plasma density in an inductively coupled plasma as a function of power and pressure for both Ar and (90:10) gas mixtures.

Some example data is shown to the right

<https://www.impedans.com/langmuir-and-octiv-application-note-lp15-oc08>



Examples are shown of the Temporal evolution of the electron density as a function of the input power in a 10 mTorr Ar pulsed plasma and as a function of the Pressure in an plasma.

# Spatial Measurement of Plasma Parameters in a Two-Chamber ICP

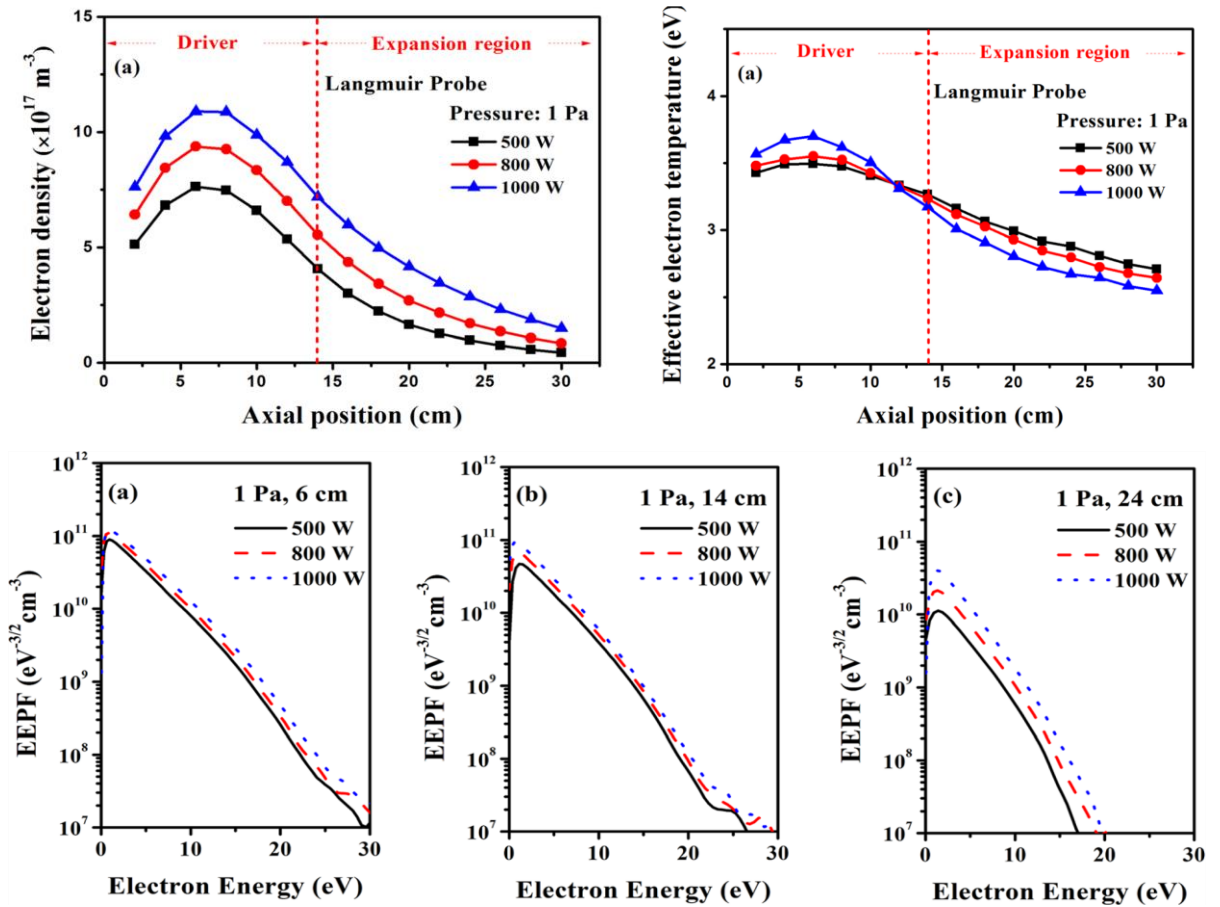
## Non-local electron kinetics and spatial transport in radio-frequency two-chamber inductively coupled plasmas with argon discharges

DOI: 10.1063/1.4986495

The objective is to measure the spatial characteristics of the plasma parameters along the axis of the chamber (results shown) and along the radial direction of the chamber (not shown here).

Some example data is shown to the right

<https://www.impedans.com/langmuir-and-octiv-application-note-lp18-oc09>



Examples of the spatial behaviour of the electron density and temperature along the axis of the chamber for a variety of powers. Also shown are some sample EEPFs at various positions for the same powers

# Langmuir Theory

# Sheath Expansion Models

## $I_i$ – The ion current for collisionless sheaths

Comprehensive studies [1 - 4] have shown (for collisionless probe sheaths) that the ion current to a cylindrical probe, incorporating sheath expansion, can be expressed with excellent accuracy as

$$I_i = I_0 a (-X)^b \quad (1)$$

where  $I_0$  is the ion flux at the sheath edge and  $X$  is the dimensionless probe potential given by  $X = (V - V_p)/kT_e$ , where  $V$  and  $V_p$  are the probe and plasma potential respectively and  $kT_e$  is the electron temperature in eV. The coefficients  $a$  and  $b$  are parameters relating to the probe radius  $r_p$ , the Debye length  $\lambda_D$  and the probe geometry. Analytical expressions for the parameters  $a$  and  $b$  have been given for a cylindrical probe, in terms of  $r_p/\lambda_D$ , by Narasimhan and Steinbruchel [4]. For a cylindrical probe:

$$\begin{aligned} a_{cyl} &= 1.18 - 0.0008 \left( \frac{r_p}{\lambda_D} \right)^{1.35} \\ b_{cyl} &= 0.0684 + (0.722 + 0.928 r_p/\lambda_D)^{-0.729} \end{aligned} \quad (2)$$

For certain probe geometries, under certain plasma conditions, the hemispherical sheath that develops around the end face of the probe tip can provide a significant contribution to the probe ion current.

Parameters  $a$  and  $b$  for the hemispherical end sheath are also

$$\begin{aligned} \text{given: } a_{sph} &= 1.98 + 4.49 \left( \frac{r_p}{\lambda_D} \right)^{1.31} \\ b_{sph} &= -2.95 + 3.61 \left( \frac{r_p}{\lambda_D} \right)^{-0.0394} \end{aligned} \quad (3)$$

The total ion current collected by real cylindrical probe is assumed to be the sum of the ion current to an ideal cylindrical probe  $I_i(cyl)$  and the ion current to a hemisphere at the end of the probe  $I_i(sph)$  and are related by

$$\frac{I_i(sph)}{I_i(cyl)} = \left( \frac{r_p}{L_p} \right) \left( \frac{a_{sph}}{a_{cyl}} \right) (-X)^{\Delta b} \quad (4)$$

where  $\Delta b = b_{sph} - b_{cyl}$  and  $L_p$  is the probe tip length. Equation 1 is initially solved for  $I_0$  using the probe current at a large negative voltage. Then  $I_i$  to the probe for all probe voltages is calculated using  $I_0$ . The electron current  $I_e$  is obtained by subtracting  $I_i$  from the probe current. Figure 1 shows an IV characteristic including the calculated ion current and electron current.

# Sheath Expansion Models

## $I_i$ – The ion current for collisionless sheaths

At higher pressures when the ions begin to undergo collisions with the neutral atoms in the probe sheath this theory fails and so a second theory is implemented.

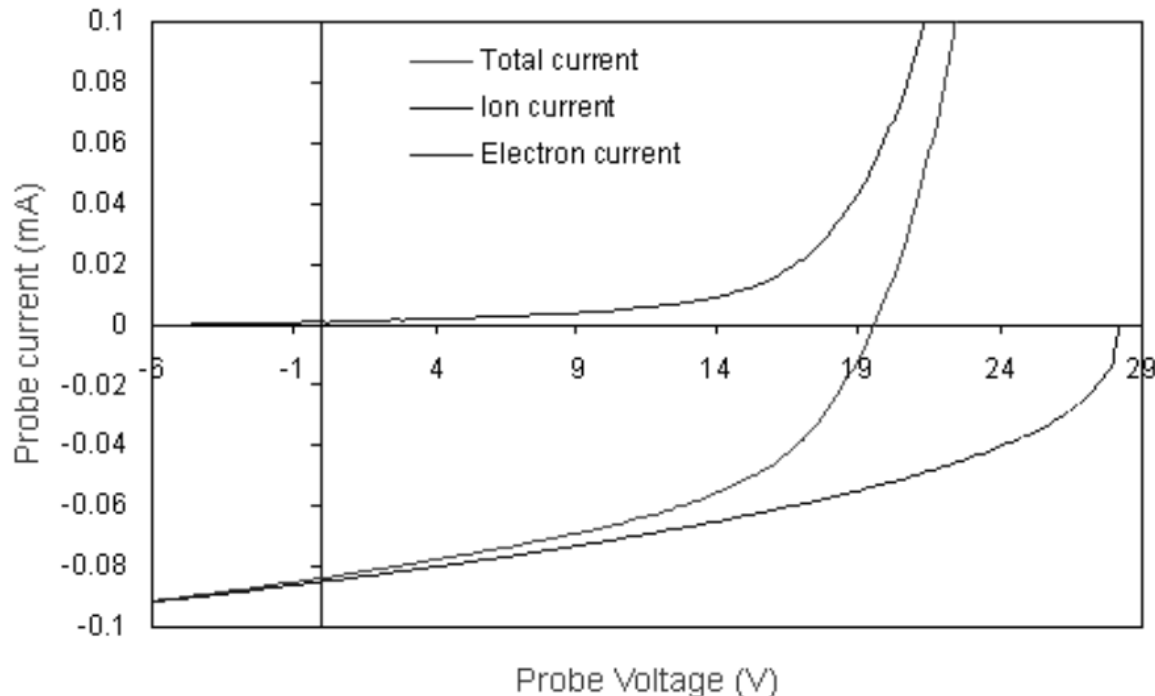


Figure 5-3: IV characteristic in the ion current region, showing total, ion and electron probe currents

## $I_i$ – The ion current for collisional sheaths

Recent studies [5-7] have led to the development of models for probe ion current in the presence of ion collisions in the sheath and have been demonstrated to work up to high pressure. One of the most accurate has been shown to be [8] that of Zakrzewski and Kopiczynski [7]. This model is expressed in terms of the collisionless model described by equations 1 and 4 as:

$$I_i = [I_0 a(-X)^b + I_i(sph)] \gamma_1 \gamma_2 \quad (5)$$

where  $\gamma_1$  and  $\gamma_2$  are factors which depend on the number of collisions in the sheath and is based on a theory proposed by Allen, Boyd and Reynolds [9] (ABR) such that:

$$\gamma_1 = \chi_i \left( \frac{I_i(ABR)}{I_i(LAF)} - 1 \right) \quad \gamma_2 = \frac{3 - 2e^{-\chi_i}}{1 + 2\chi_i} \quad \text{If } \chi_i < 1 \quad (6)$$

$$\gamma_1 = \frac{I_i(ABR)}{I_i(LAF)} \quad \gamma_2 = \frac{3 - e^{-\chi_i}}{2(1 + 2\chi_i)} \quad \text{If } \chi_i > 1$$

# Sheath Expansion Models

## $I_i$ – The ion current for collisional sheaths

where  $I_i(ABR)$  is the current to the probe in the collisional regime,  $I_i(LAF)$  is the current to the probe in the collisionless regime given by equation 1, and  $\chi_i$  is the number of collisions in the sheath, defined by

$$\chi_i = \frac{r_s - r_p}{\lambda_i} \quad (7)$$

Where  $r_s$  and  $r_p$  are the sheath and probe radii respectively and  $\lambda_i$  is the ion mean free path. An analytical fit for  $r_s - r_p$  is used [7]:

$$r_s - r_p = \lambda_D \sqrt{0.59 + 1.86 r_p / \lambda_D (-X + 3.5) - 4} \quad (8)$$

We use the analytical expression for  $I_i(ABR)$  proposed by Klagge and Tichy [5] i.e.  $I_i(ABR) = a (-X/b)^c$ , with coefficients:

$$\begin{aligned} a &= (r_p + 0.6)^{0.05} + 0.04 \\ b &= 0.09(e^{\lambda_D/r_p} + 0.08) \\ c &= (r_p/\lambda_D + 3.1)^{-0.6} \end{aligned} \quad (9)$$

The implementation of this model allows the Langmuir Probe system to give accurate measurements up to discharge pressure of 10 Torr.

## References

- [1] J.G. Laframboise, Report No. 100, University of Toronto UTIAS, 1966
- [2] [Ch. Steinbruchel, Vac. Sci. Technol. A, 8, 1663, 1990](#)
- [3] [A. Karamcheti and Ch. Steinbruchel, Vac. Sci. Technol. A, 17, 3051, 1999](#)
- [4] [G. Narasimhan and Ch. Steinbruchel, Vac. Sci. Technol. A, 19, 376, 2001](#)
- [5] [S. Klagge and M. Tichy, Czech. J. Phys., Sect. B, 35, 988, 1985](#)
- [6] L. Talbot and Y.S. Chou, 6th Rarefied Gas Dynamics Conference ed. Academic Press, New York, 1723, 1966
- [7] [Z. Zakrzewski and T. Kopiczynski, Plasma. Phys, 16, 1195, 1974](#)
- [8] [A. Rousseau, E. Teboul and S. Bechu, J. App. Phys, 98, 083306, 2005](#)
- [9] [J.E. Allen, R.L.F. Boyd, and P. Reynolds, Proc. Phys. Soc. London, Sect. B, 70, 112, 1957](#)

# Single Probe: Plasma Parameter Equations

**Plasma Potential (Intersecting Slope method):**

$$V_p = \frac{-b + \ln(I(V_{max})) - \frac{V_{max}}{kT_e}}{a - \frac{1}{kT_e}} \quad (10)$$

**Electron Temperature:**

$$\frac{1}{kT_e} = \frac{I(V_p)}{\int_{V_f}^{V_p} I_e(V) dV} \quad (11)$$

**Electron Density:**

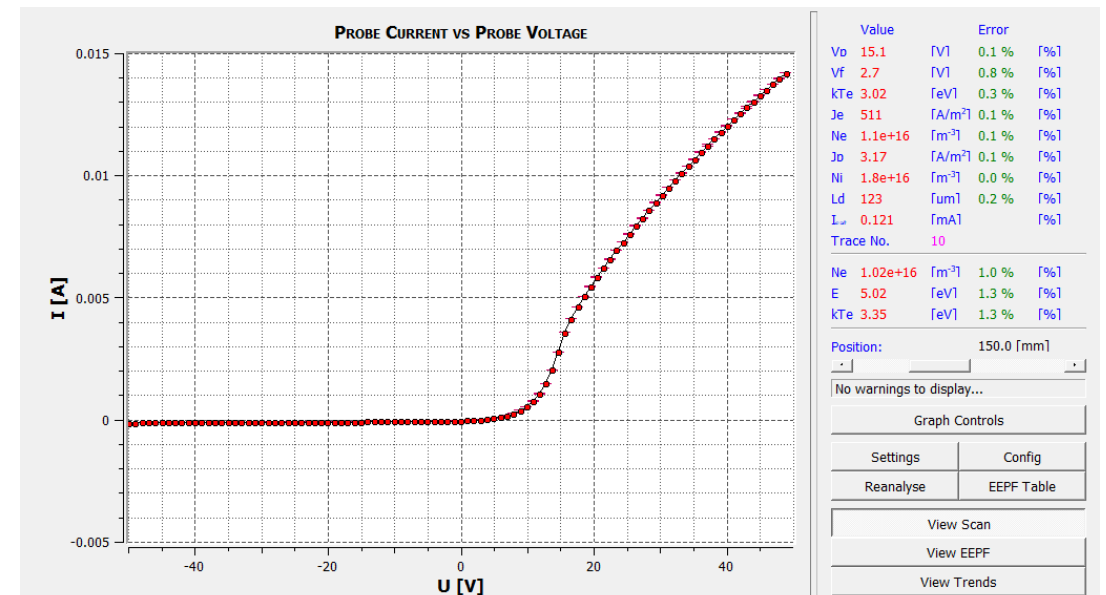
$$e = \frac{I(V_p)}{A_p} \sqrt{\frac{2\pi m_e}{e^2 kT_e}} \quad (12)$$

**Ion flux:**

$$I_0 = \frac{I(-80V)}{a_{cyl}(-X)^{b_{cyl}} \left(1 + \frac{r_p}{\lambda_D} \frac{a_{sph}}{a_{cyl}} (-X)^{\Delta b}\right) \gamma_1 \gamma_2} \quad (13)$$

**Ion Density:**

$$n_i = \frac{I_0}{A_p} \sqrt{\frac{2\pi m_i}{e^2 kT_e}} \quad (14)$$



# Single Probe: EEPF Equations

## Druyvesten Equation

$$n(\varepsilon) = n_e f(\varepsilon) = \frac{2 I''}{e A_p} \sqrt{\frac{2m_e}{e}} \quad (15)$$

## Electron Density (from EEPF Characteristic):

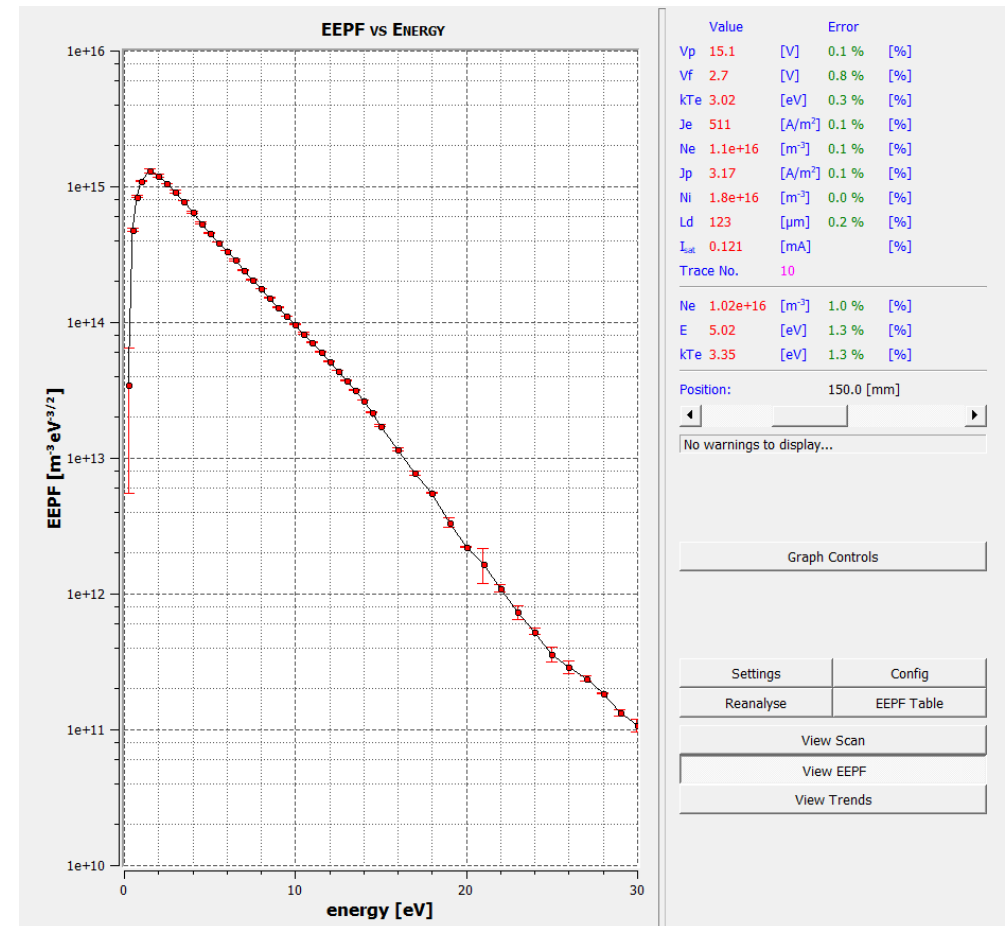
$$n_e = \int_0^{\varepsilon_{max}} n(\varepsilon) d\varepsilon \quad (16)$$

## Average Electron Energy:

$$\langle \varepsilon \rangle = \int_0^{\varepsilon_{max}} \varepsilon n(\varepsilon) d\varepsilon \quad (17)$$

## Electron temperature (from EEPF Characteristic):

$$kT_e = \frac{2}{3} \langle \varepsilon \rangle \quad (18)$$



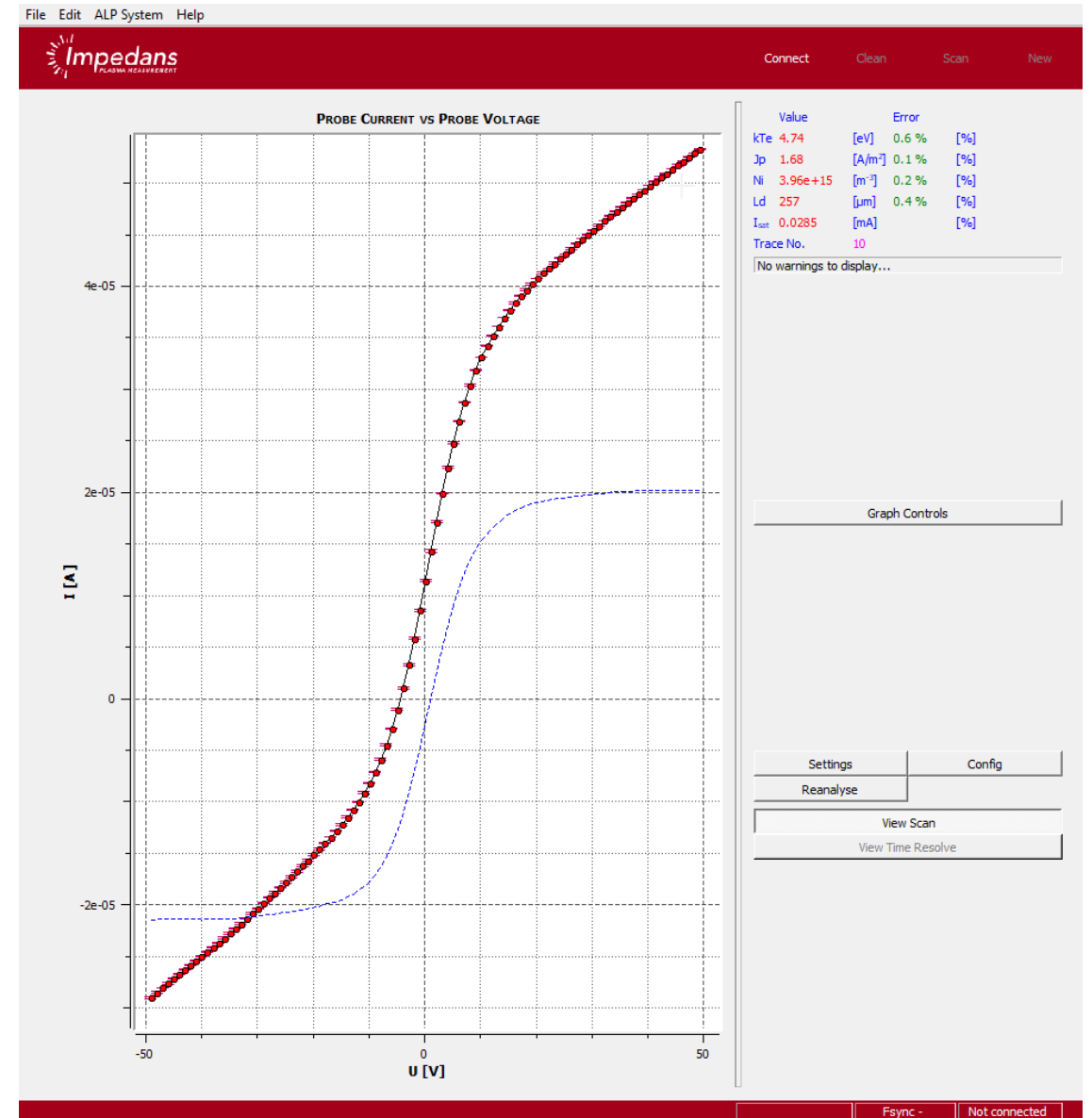
# Double Probe: Plasma Parameter Equations

## Electron Temperature:

$$\frac{eV}{kT_e} = 2 \tanh^{-1} \left( \frac{I_{corrected}}{I_{i,sat}} \right) \quad (19)$$

## Ion Density:

$$n_i = \frac{I_{i,sat}}{A} \sqrt{\frac{2\pi m_i}{e^2 kT_e}} \quad (20)$$



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